

L Number	Hits	Search Text	DB	Time stamp
1	7715	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:02
2	0	("land(cap\$4adjlayer)").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:04
3	597	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:25
4	271	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (dielectric or insulat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:05
5	63	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (dielectric or insulat\$3)) and (plasma same etch\$3 same (cap\$3 adj layer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:06
6	85	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (dielectric or insulat\$3)) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:25
7	17	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (dielectric or insulat\$3)) and (plasma same etch\$3 same (cap\$3 adj layer)) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:07
8	16	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (dielectric or insulat\$3)) and (plasma same etch\$3 same (cap\$3 adj layer)) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2) and (oxygen or "o.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:07
9	5	((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (dielectric or insulat\$3)) and (plasma same etch\$3 same (cap\$3 adj layer)) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2) and ((oxygen or "o.sub.2") same (sio or (silicon adj oxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:08

10	5	(((((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer)) and (plasma same etch\$3 same (dielectric or insulat\$3))) and (plasma same etch\$3 same (cap\$3 adj layer))) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2)) and (oxygen or "o.sub.2")) and ((oxygen or "o.sub.2") same (sio or (silicon adj oxide))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:08
11	2	(((((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer)) and (plasma same etch\$3 same (dielectric or insulat\$3))) and (plasma same etch\$3 same (cap\$3 adj layer))) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2)) and (oxygen or "o.sub.2")) and ((oxygen or "o.sub.2") same (sio or (silicon adj oxide)))) and clean\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:22
12	1	(((((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer)) and (plasma same etch\$3 same (dielectric or insulat\$3))) and (plasma same etch\$3 same (cap\$3 adj layer))) and (plasma same etch\$3 same (cap\$3 adj layer) same polymer or residu\$2)) and (oxygen or "o.sub.2")) and ((oxygen or "o.sub.2") same (sio or (silicon adj oxide)))) and ((clean\$3 or remove) near10 (silicon adj oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:24
13	602	((438/902) or (438/906) or (438/963)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:25
14	56	((438/902) or (438/906) or (438/963)).CCLS.) and (cap\$4 adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:25
15	0	((438/902) or (438/906) or (438/963)).CCLS.) and (cap\$4 adj layer) and (plasma same etch\$3 same (cap\$3 adj layer) same (polymer or residu\$2))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:26
-	7518	((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/24 15:02
-	273	((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (capping adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 02:13
-	175	((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (capping adj layer)) and (etch\$3 same (capping adj layer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 02:14

-	61	(((((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (capping adj layer)) and (etch\$3 same (capping adj layer))) and (plasma same oxygen))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 02:14
-	4	(((((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (capping adj layer)) and (etch\$3 same (capping adj layer))) and (plasma same oxygen)) and clean\$3 and ((in adj2 situ) or (ex adj2 situ))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 02:15
-	32	(((((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (capping adj layer)) and (etch\$3 same (capping adj layer))) and (plasma same oxygen)) and clean\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 15:59
-	0	(((((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (capping adj layer)) and (etch\$3 same (capping adj layer))) and (plasma same oxygen)) same clean\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 15:59
-	1025	clean\$3 same(contact or via) same oxygen same plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 16:00
-	548	(clean\$3 same(contact or via) same oxygen same plasma) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 16:01
-	49	((clean\$3 same(contact or via) same oxygen same plasma) and 438/\$.ccls.) and ((cap or capping) adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 16:01